



520.35237VX3

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: T. KAJI, et al.
Application No.: 10/052,538
Filed: January 23, 2002
For: PLASMA PROCESSING APPARATUS PROCESSING METHOD
Art Unit: 1763
Examiner: A. M. Crowell

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SUBMISSION OF AMENDMENT WITH RCE UNDER 37 CFR § 1.114

Mail Stop RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

May 7, 2003

Sir:

In accordance with the provisions of 37 CFR 1.114, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 63

Please replace Paragraph 3, starting on line 19 and bridging page 64 with the following new paragraph:

As described above, in order to improve micro workability of a sample, it is preferable that a plasma generating high frequency electric power source 16 has a higher frequency and discharge under a low gas pressure is stabilized. In the